Notice of Allowability	Application No.	Applicant(s)	
	10/064,098	ALLEN ET AL.	
	Examiner	Art Unit	
	Helen Rossoshek	2825	
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this a or other appropriate communicating IGHTS. This application is subjection.	application. If not included ion will be mailed in due course. Th	
1. X This communication is responsive to Application filed 06/1	<u>1/2002</u> .		
2. 🔀 The allowed claim(s) is/are <u>1-27</u> .			
3. $igspace$ The drawings filed on <u>10/28/2002</u> are accepted by the Exa	miner.		
4. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have international Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submed in INFORMAL PATENT APPLICATION (PTO-152) which give including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1) each sheet. Replacement sheet(s) should be labeled as such in the International Report of the Paper No. INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT in the International Report of the Paper No. INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT in the International Report of the Paper No. In the International Report of the Paper No. International Report of the	e been received. e been received in Application No. cuments have been received in the of this communication to file a rep dENT of this application. itted. Note the attached EXAMINE es reason(s) why the oath or decla set be submitted. son's Patent Drawing Review (PT s Amendment / Comment or in the declaration. 84(c)) should be written on the draw the header according to 37 CFR 1.12 sit of BIOLOGICAL MATERIAL	is national stage application from the stage app	.
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summa Paper No./Mail □ 8), 7. ☐ Examiner's Amen 8. ☑ Examiner's State 9. ☐ Other	Date	<u>/</u>

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DETAILED ACTION

1. This office action is in response to the Application 10/064,098 filed 06/11/2002.

2. Claims 1-27 are pending in the Application.

Allowable Subject Matter

3. Claims 1-27 allowed. The following is an examiner's statement of reasons for allowance: in a method of reducing shorts in an integrated circuit having cells, the prior art does not include a step of creating a cloned cell by removing a via identified as faulty from an original cell.

4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Bracha et al. (US Patent 5,798,937) discloses the redundant via software scans for places in close proximity to the critical via where redundant vias can be placed electrically in parallel to the critical via; in another form, the redundant via software searches for areas that will allow the contact opening of the critical via to be extended or widened to improve the reliability of the critical via, wherein significant increase of integrated circuit yield has been observed using the redundant via methods taught herein, but lacks evaluating an original cell containing a faulty via to determine if

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a redundant via exists for the faulty via; and removing the faulty via from the original cell to create a cloned cell. Papadopoulou et al. (US Patent 6,247,853) discloses providing an efficient method to compute critical area and critical regions for via blocks by characterizing the critical region of a via shape for several geometries as a function of the defect size, wherein in certain geometries (including the Euclidean), the critical region of one via shape grows uniformly as the defect radius increases; based on these characterizations, providing an incremental algorithm to compute critical area for via blocks which is valid for several geometries; wherein the incremental computation is efficient because it takes advantage of the hierarchical structure typical of VLSI designs. in which repeated geometric patterns are represented by cells consisting of shapes and transforms on usages of those cells; but lacks evaluating an original cell containing a faulty via to determine if a redundant via exists for the faulty via; and removing the faulty via from the original cell to create a cloned cell. Regan (US Patent Application Publication 2003/0084418) discloses a process for modifying the design of integrated circuits including the steps of mapping cells of an old circuit against a library of new cells and replacing at least some of the old cells with new cells having the same logical function as the old cells, while maintaining the electrical connections between those cells, wherein the geometry of the electrical connections between the cells is then rerouted, but lacks evaluating an original cell containing a faulty via to determine if a redundant via exists for the faulty via; and removing the faulty via from the original cell to create a cloned cell. Anderson et al. (US Patent 6,415,421) discloses an integrated verification and manufacturability tool provides more efficient verification of integrated

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device designs than verification using several different verification tools; the integrated

verification and manufacturability includes a hierarchical database to store shared

design data accessed by multiple verification tool components (e.g., layout versus

schematic, design rule check, optical process correction, phase shift mask assignment

and machine language conversion), wherein the hierarchical representation provided by

modified database provides several performance advantages, but lacks identifying

faulty vias as ones having a chance of shorting that is above a predetermined threshold;

evaluating an original cell containing a faulty via to determine if a redundant via exists

for the faulty via; and removing the faulty via from the original cell to create a cloned

cell.

6. Any inquiry concerning this communication or earlier communications from

the examiner should be directed to Helen Rossoshek whose telephone number is 571-

272-1905. The examiner can normally be reached on 7:00-4:00.

7. If attempts to reach the examiner by telephone are unsuccessful, the

examiner's supervisor, Matthew S Smith can be reached on 571-272-1907. The fax

phone number for the organization where this application or proceeding is assigned is

703-872-9306.

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8. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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